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Electronics Manufacturing Technology Symposium, 1997., Twenty-First IEEE/International , 13-15 Oct. 1997

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[\[Abstract\]](#) [\[PDF Full-Text \(364 KB\)\]](#) IEEE CNF

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3 Test structure for fixing OPC of 200 nm pitch via chain using inner a outer dummy via array
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Pages:146 - 147

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Kyoung-Ah Jeon; Ji-Yong Yoo; Jun-Taek Park; Hyeongsu-Kim; Ilsin An; Hye-Oh;
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7 Improvement of CD uniformity in 180 nm LSI manufacturing by optimizing illumination system

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